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(21) International Application Number: PCT/US97/04103 (22) International Filing Date: 6 March 1997 (06.03.97) (30) Priority Data: 60/025,174 7 March 1996 (07.03.96) US (71) Applicant: THE B.F. GOODRICH COMPANY, (US/US); 4020 Kinross Lakes Parkway, Richfield, OH 44286 (US) (72) Inventors: GOODALL, Brian, L. 3959 Clover Hill Road, Akron, OH 44333 (US). JAYARAMAN, Saikumar, Apartment 304, 4188 Americana Drive, Cuyahoga Falls, OH 44224 (US). SHICK, Robert, A. 10375 Pamela Drive, Strongsville, OH 44136 (US). RHODES, Larry, F. 3036 Vincent Road, Silverlake, OH 44224 (US). (74) Agents: DUNLAP, Thoburn, T. et al.; The B.F. Goodrich Company, 9921 Brecksville Road, Brecksville, OH 44141-3289 (US).		(81) Designated States: AL, AM, AU, AZ, BB, BG, BR, BY, CA, CN, CZ, EE, GE, HU, IL, IS, JP, KE, KG, KR, KZ, LK, LR, LS, LT, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, RO, RU, SD, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN, ARIPO patent (GH, KE, LS, MW, SD, SZ, UG), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i> <i>Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
(54) Title: PHOTORESIST COMPOSITIONS COMPRISING POLYCYCLIC POLYMERS WITH ACID LABILE PENDANT GROUPS (57) Abstract The present invention relates to a radiation sensitive photoresist composition comprising a photoacid initiator and a polycyclic polymer comprising repeating units that contain pendant acid labile groups. Upon exposure to an imaging radiation source, the photoacid initiator generates an acid which cleaves the pendant acid labile groups effecting a polarity change in the polymer. The polymer is rendered soluble in an aqueous base in the areas exposed to the imaging source.		